

Application No.: 09/849,460  
Docket No.: JCLA6212

metal etching residues, comprising steps as follows:

- Amended*
- a substrate is provided;
  - a barrier layer is formed on the substrate;
  - a pre in-situ metal layer is formed on the barrier layer;
  - a first metal layer is formed immediately after the pre in-situ metal layer is formed and in the same vacuum surrounding as the one in which the pre in-situ metal layer is formed; and
  - a photolithography and etching step is performed to define the barrier layer, the pre in-situ metal layer and the first metal layer.

*A2*

12. (Once Amended) A process for forming a conducting structure layer, comprising the following steps:

- a substrate is provided;
- a pre in-situ metal layer is formed on the substrate;
- a metal layer is formed on the pre in-situ metal layer; and
- a photolithography and etching step is performed to define the pre in-situ metal layer and the metal layer.